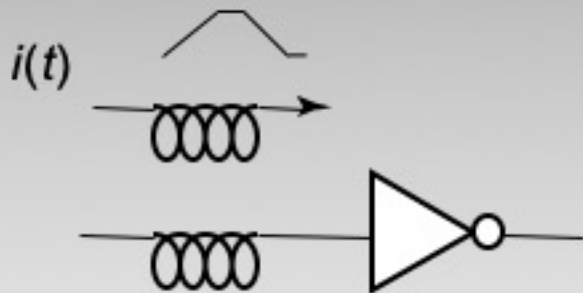


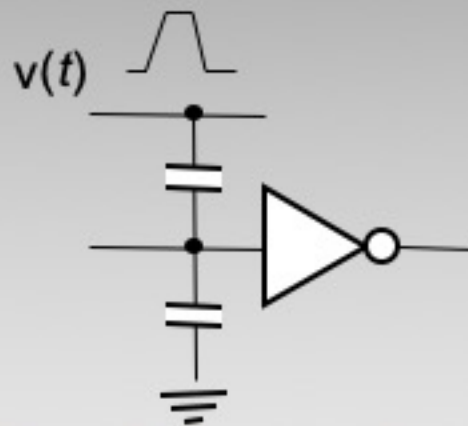
# Digital ICs — Lectures

1) <b>Introduction</b> [Ch. 1]	TSEI03/TSTE86
2) <b>Devices</b> [Ch. 3, 4]	TSEI03/TSTE86
3) <b>Interconnect</b> [Ch. 4, 9]	TSTE86
4) <b>Circuits</b> [Ch. 5]	TSEI03/TSTE86
5) <b>Combinational logic</b> [Ch. 6]	TSEI03/TSTE86
6) <b>Sequential circuits</b> [Ch. 7]	TSEI03/TSTE86
7) <b>Synchronization</b> [Ch. 10]	TSTE86
8) <b>Adders</b> [Ch. 11]	TSEI03/TSTE86
9) <b>Multipliers</b> [Ch. 11]	TSTE86
10) <b>Memory</b> [Ch. 12]	TSEI03/TSTE86
11) <b>Manufacturing</b> [Ch. 2]	TSTE86
12) <b>System design</b> [Ch. 8]	TSTE86

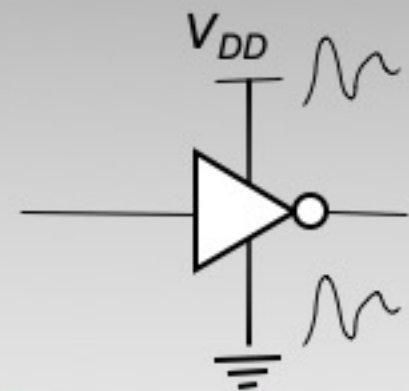
# On-Chip Noise



**Inductive coupling**

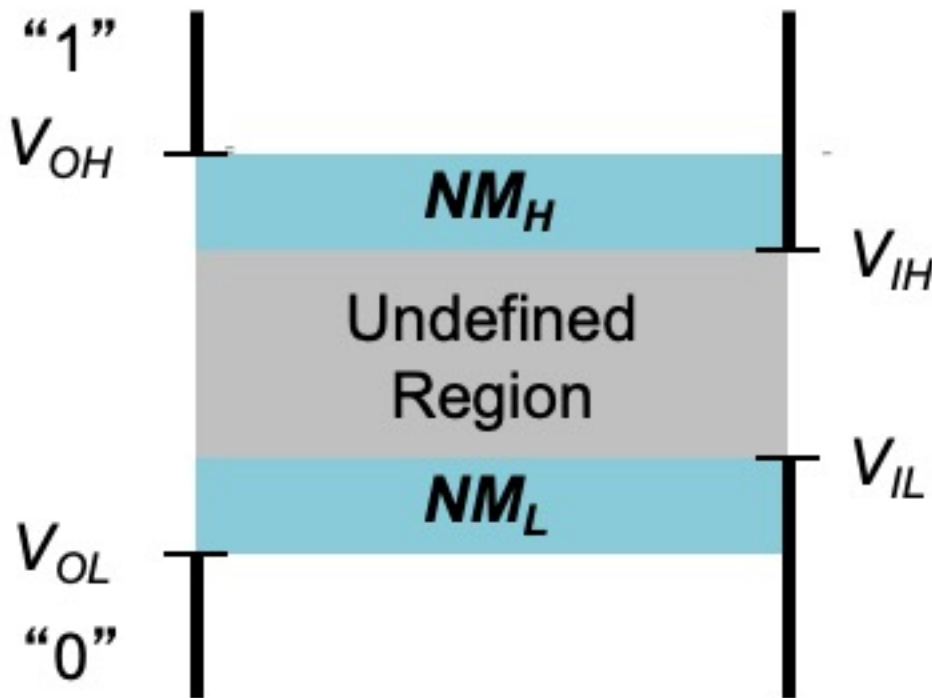
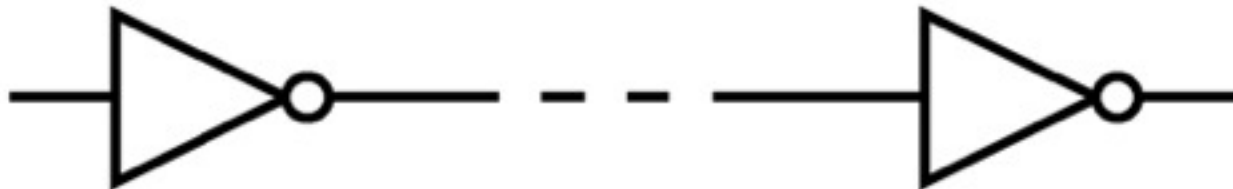


**Capacitive coupling**



**Power and ground noise**

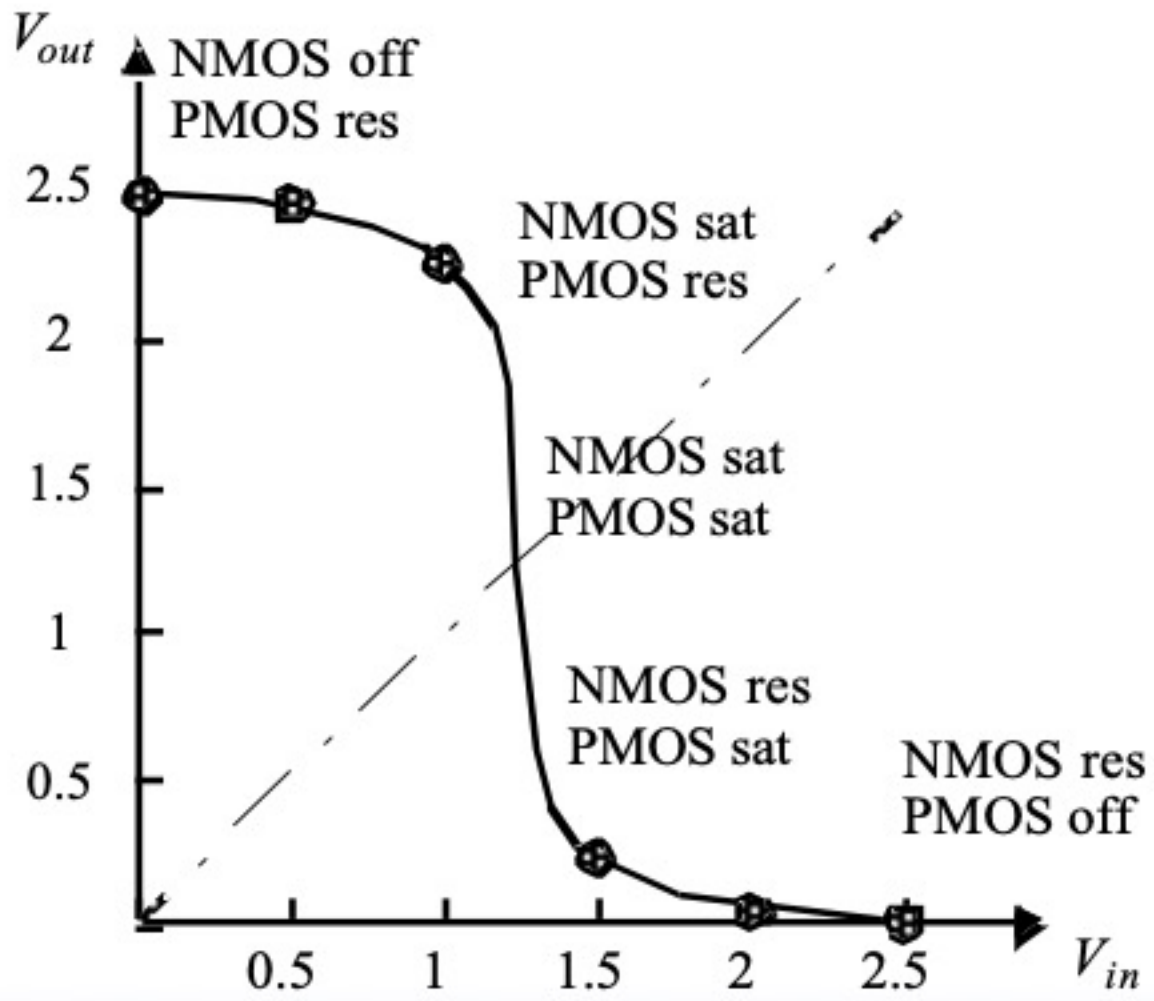
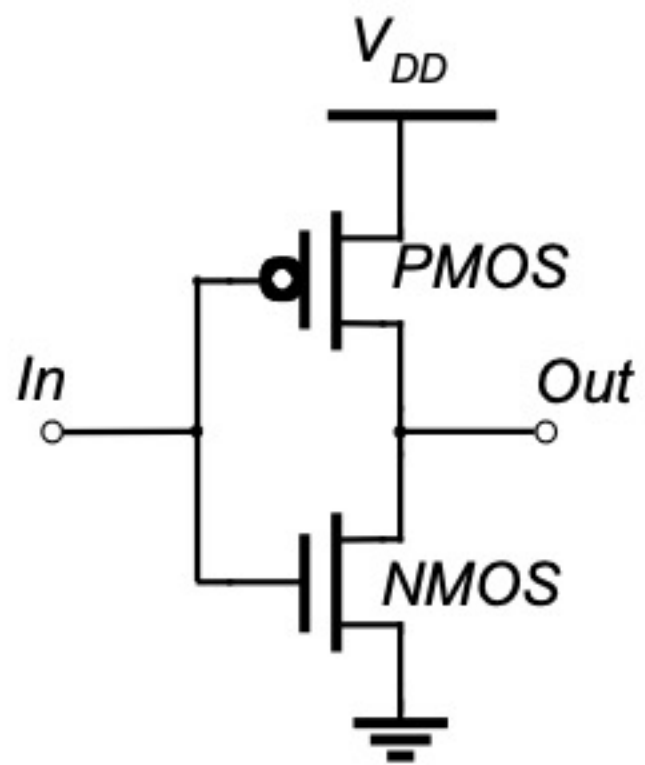
# Noise Margins



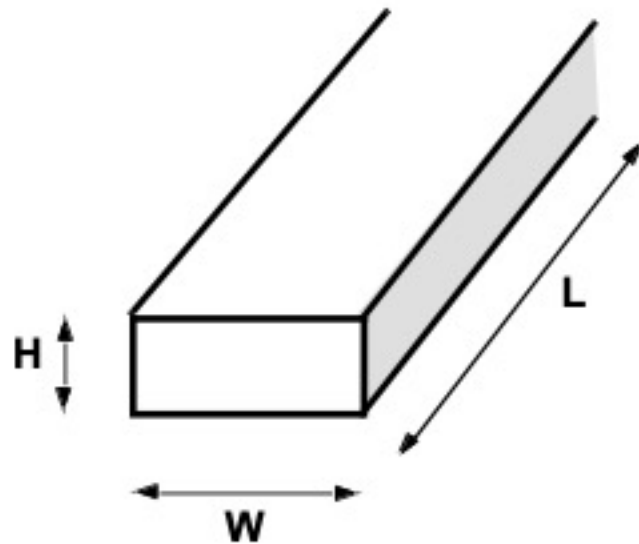
Noise margin high:  
 $NM_H = V_{OH} - V_{IH}$

Noise margin low:  
 $NM_L = V_{IL} - V_{OL}$

# CMOS Inverter

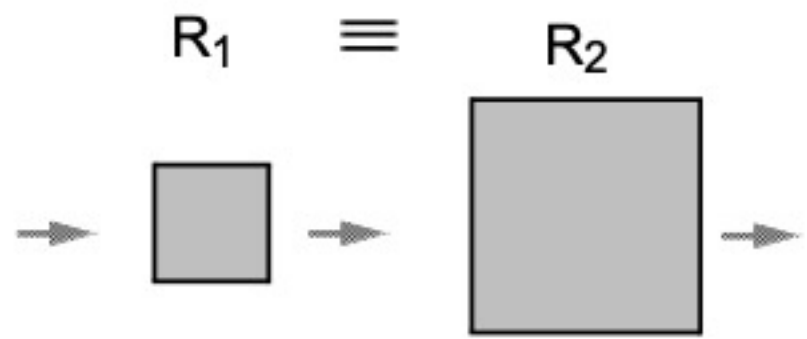


# Wire Resistance

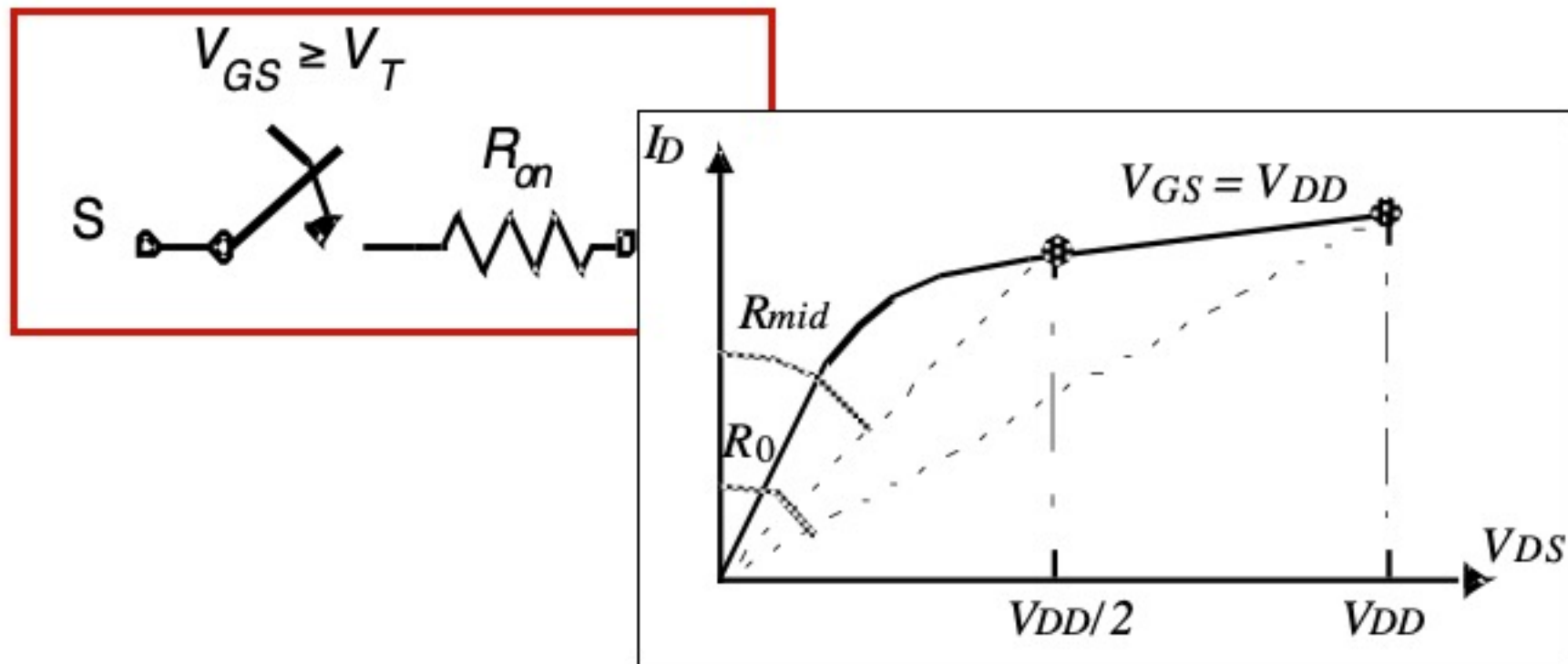


$$R = \frac{\rho L}{HW}$$

Sheet Resistance  
 $R_0$

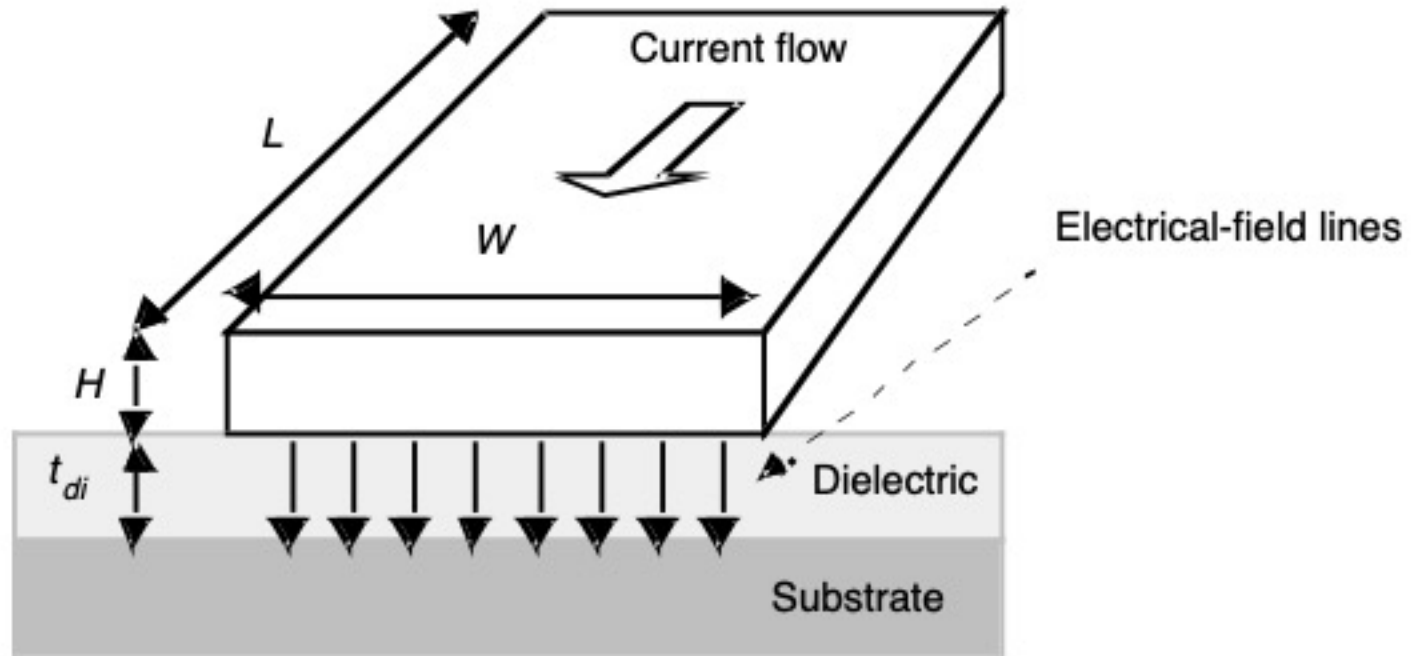


# Resistance of the MOSFET Channel



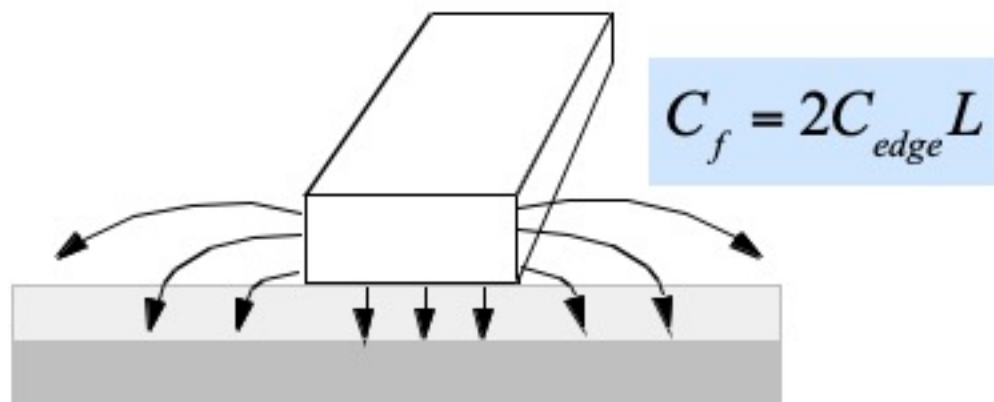
**Example :** assuming velocity saturation in range  $V_{DD} \geq V_{DS} \geq \frac{V_{DD}}{2} \Rightarrow R_{on} = \frac{1}{2} \left( \frac{V_{DD}}{I_{DSAT}} + \frac{V_{DD}/2}{I_{DSAT}} \right) = \frac{3}{4} \cdot \frac{V_{DD}}{I_{DSAT}}$

# Parallel Plate Capacitance



$$C_{pp} = \epsilon_{di} \frac{WL}{t_{di}} = C_{area} WL$$

# Fringing Capacitance

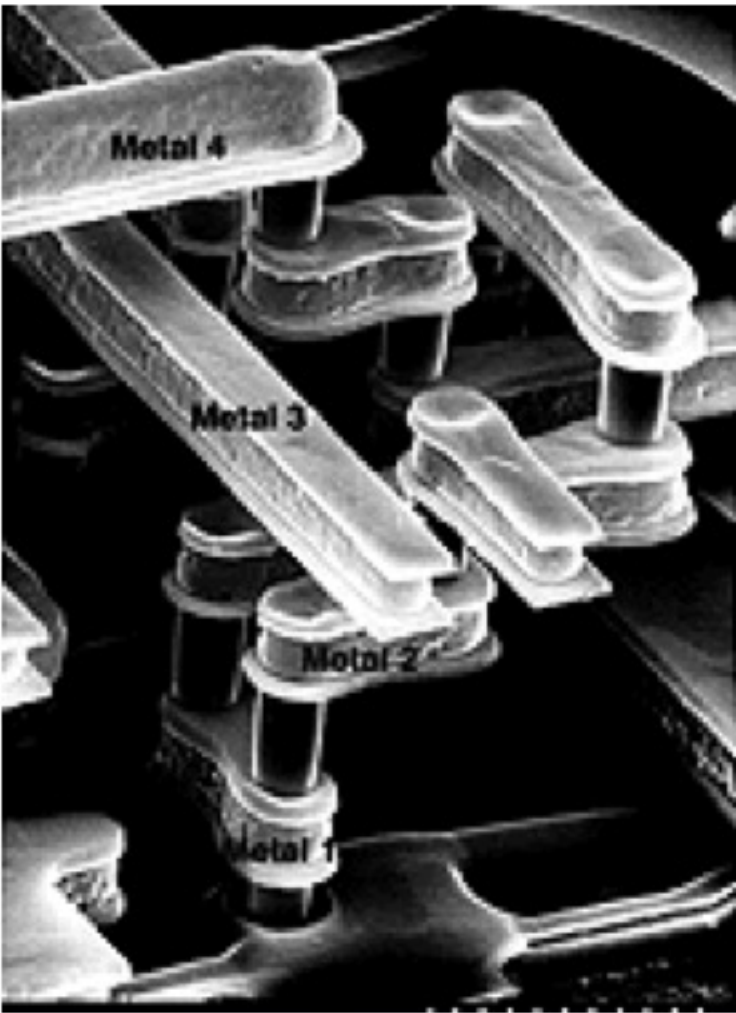


Total wire capacitance:

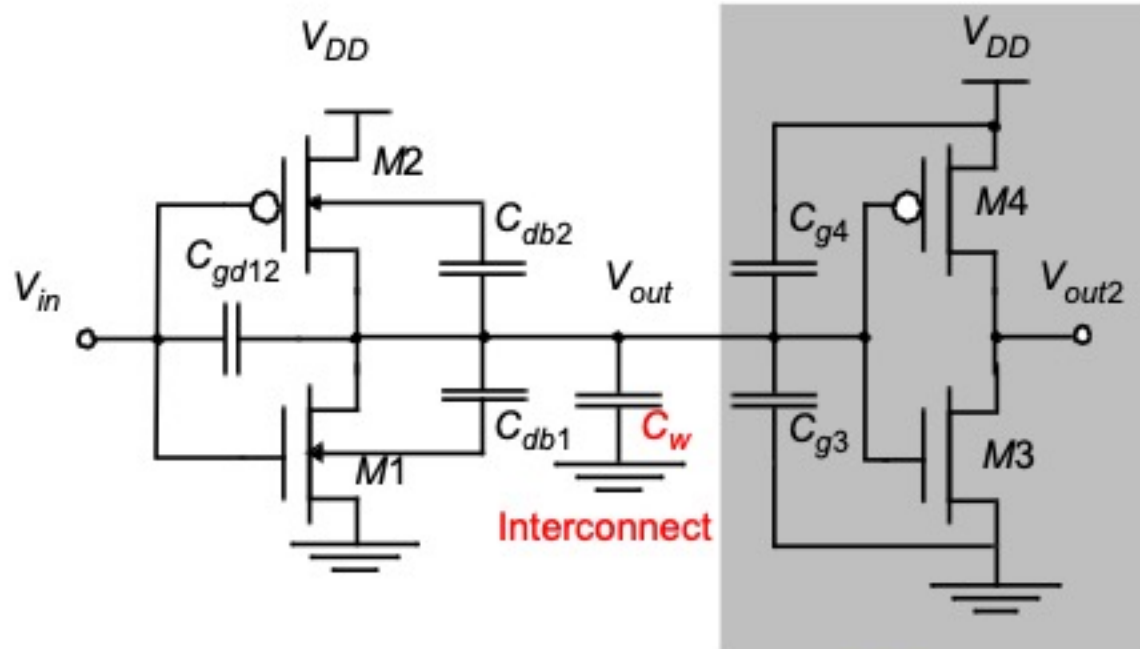
$$C_{wire} = C_{pp} + C_f = C_{area} WL + 2C_{edge} L$$



# Interconnect



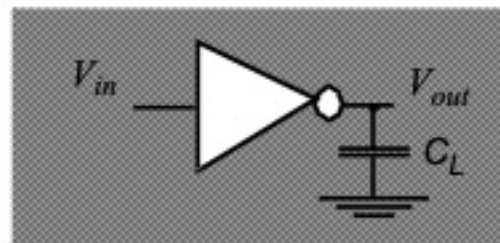
# Capacitive Load



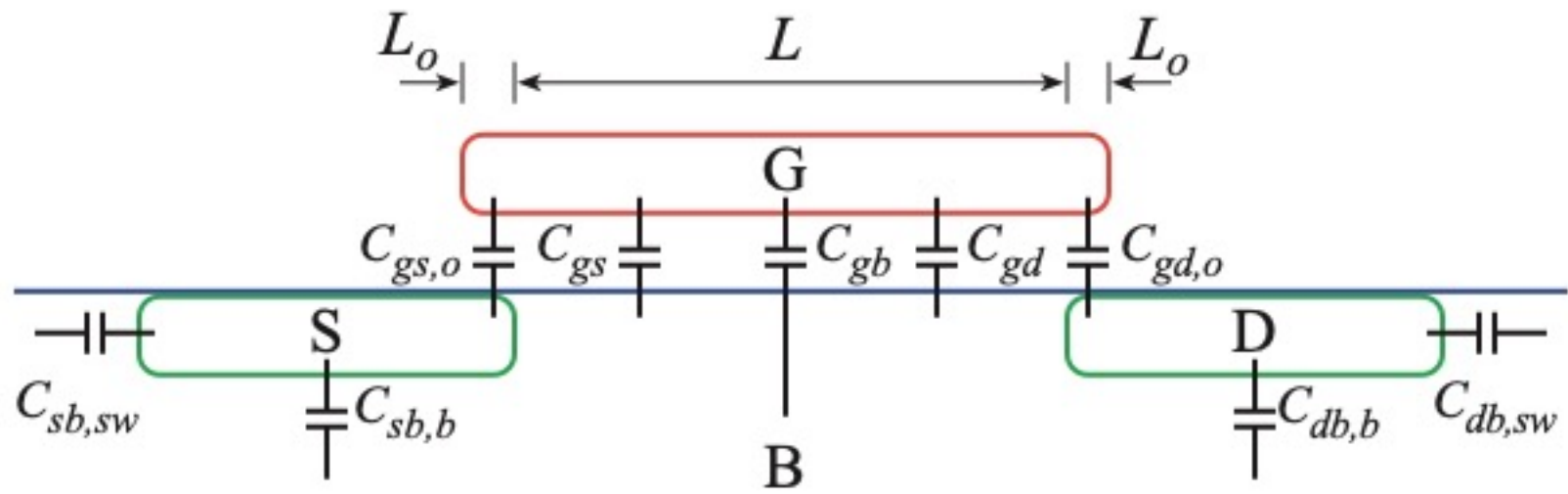
Interconnect

Fanout

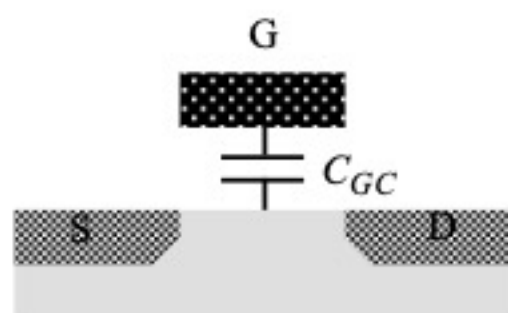
Simplified Model



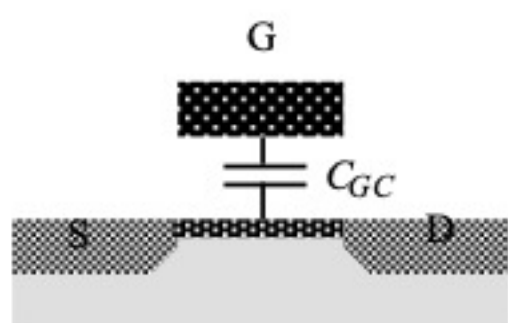
# Parasitic MOSFET Capacitances



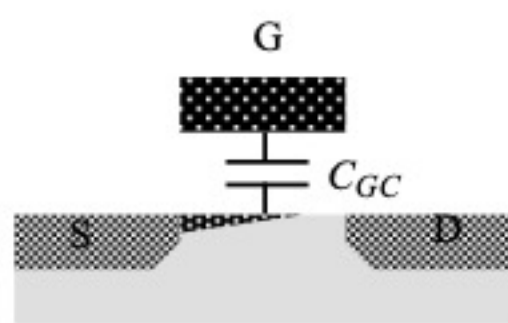
# Gate Capacitance



Cut-off



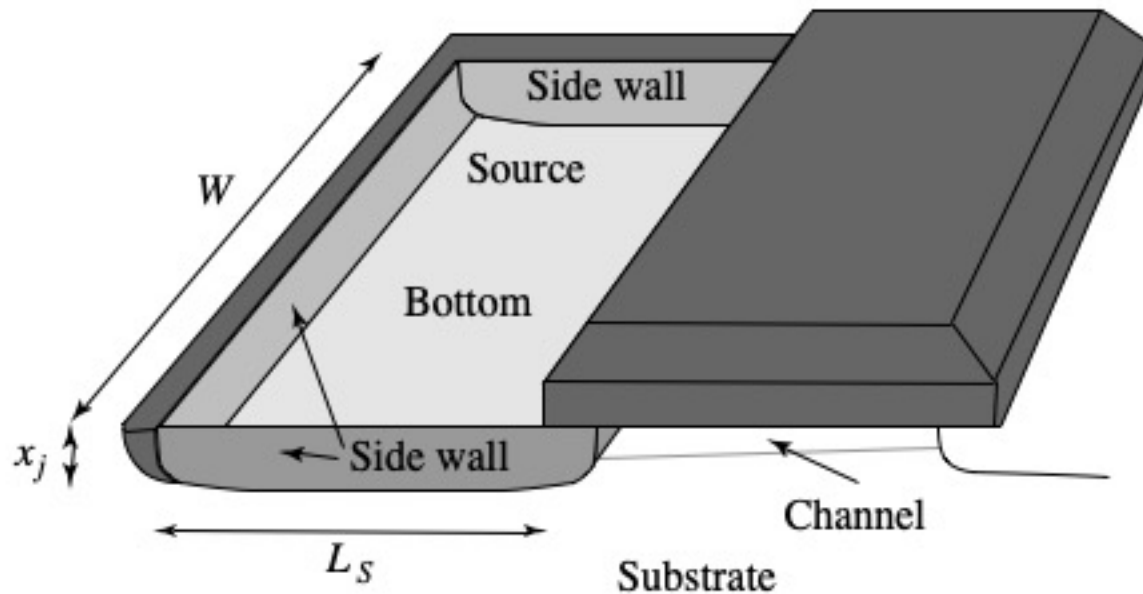
Resistive



Saturation

Operation Region	$C_{gb}$	$C_{gs}$	$C_{gd}$
Cutoff	$C_{ox}WL_{eff}$	0	0
Triode	0	$C_{ox}WL_{eff}/2$	$C_{ox}WL_{eff}/2$
Saturation	0	$(2/3)C_{ox}WL_{eff}$	0

# Diffusion Capacitance



$$\begin{aligned} C_{diff} &= C_{bottom} + C_{sw} = C_j \times AREA + C_{jsw} \times PERIMETER \\ &= C_j L_S W + C_{jsw} (2L_S + W) \end{aligned}$$

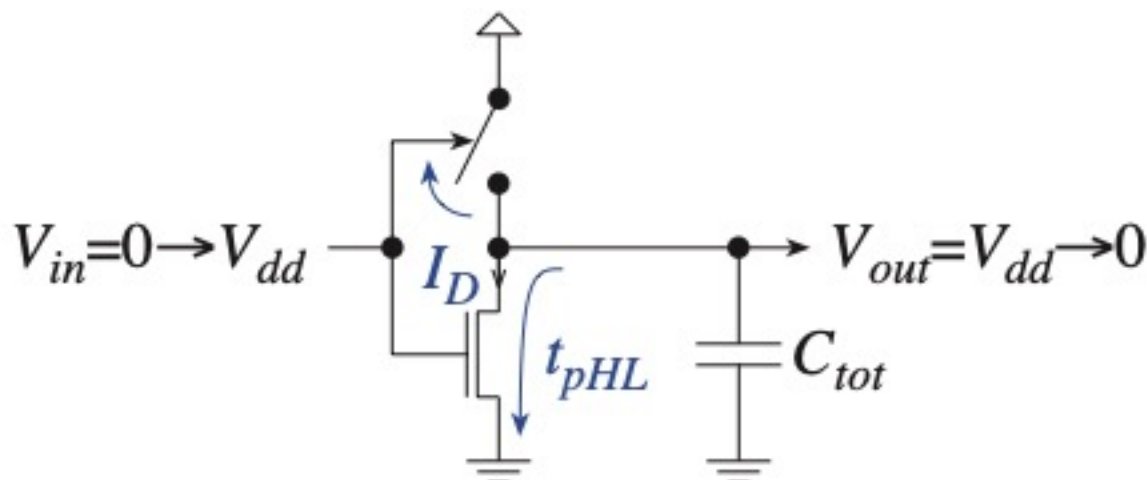
# Linearizing the Junction Capacitance

Replace non-linear capacitance by  
large-signal equivalent linear capacitance

$$C_{eq} = \frac{\Delta Q_j}{\Delta V_D} = \frac{Q_j(V_{high}) - Q_j(V_{low})}{V_{high} - V_{low}} = K_{eq} C_{j0}$$

$$K_{eq} = \frac{-\phi_0^m}{(V_{high} - V_{low})(1 - m)} [(\phi_0 - V_{high})^{1-m} - (\phi_0 - V_{low})^{1-m}]$$

# Propagation Delay



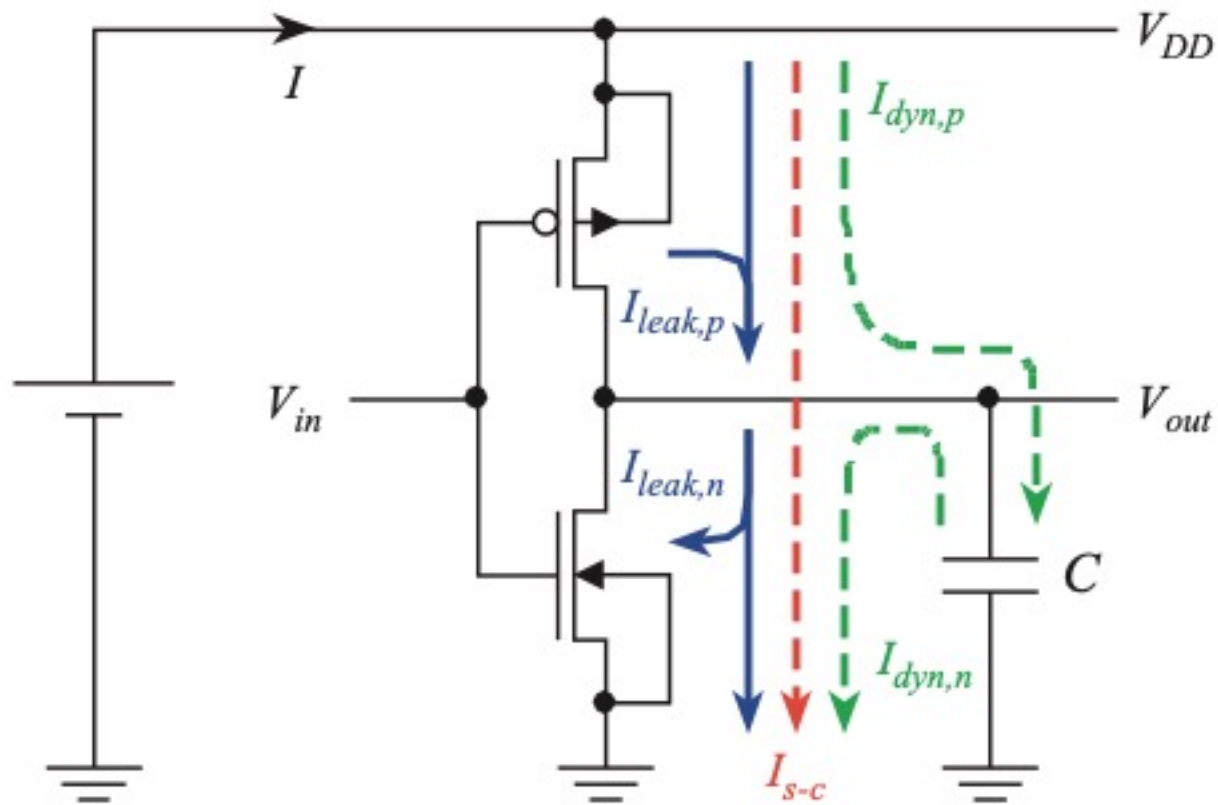
Method 1: estimate average  $R_{DS}$

$$t_{pHL} \approx 0.69 R_{DS} C_{out} \approx 0.69 \frac{R_{DS}(V_{DD}) + R_{DS}(V_{DD}/2)}{2} C_{out}$$

Method 2: estimate average  $I_D$

$$t_{pHL} \approx \Delta Q / I_D \approx \frac{C_{out} V_{DD} - C_{out} V_{DD}/2}{[I_D(V_{DD}) + I_D(V_{DD}/2)]/2}$$

# Power Dissipation





# Energy and Energy-Delay

Power-Delay Product (PDP) =

$$E = \text{energy per operation} = P_{av} \times t_p$$

Energy-Delay Product (EDP) =

$$\text{quality metric of gate} = E \times t_p$$